

**Amendments to the Claims:**

1. (Currently amended) A front-end array process for making a liquid crystal display panel, comprising:

depositing a molybdenum-containing metal layer on a glass substrate, wherein said

5 molybdenum-containing metal layer is a dual-metal layer;

forming a patterned photoresist on said molybdenum-containing metal layer, wherein said patterned photoresist defines a gate and word line array pattern; and

using said patterned photoresist as an etching mask, uniformly etching said molybdenum-containing metal layer to form said gate and word line array pattern

10 having substantially oblique sidewalls, wherein said etching of said molybdenum-containing metal layer uses gas mixture, wherein said etching of said molybdenum-containing metal layer is detected by an end-point detection method.

2. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein after said etching of said molybdenum-containing metal layer, an over etching is carried out.

3. (Previously presented) The front-end array process for making a liquid crystal display panel according to claim 1 wherein fluorine/oxygen containing gas mixture is SF<sub>6</sub>/O<sub>2</sub> having a ratio of about 700sccm/300sccm.

4. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said etching of said molybdenum-containing metal layer is executed under a process pressure higher than 25 mTorr.

5. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said etching of said molybdenum-containing metal layer is further controlled by a source power, a bias power, process pressure, oxygen flowrate and flowrate of fluorine containing gas.

6. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said molybdenum-containing metal layer is a dual-metal

layer.

7. (Previously presented) The front-end array process for making a liquid crystal display panel according to claim 6 wherein said dual-metal layer is Mo/AlNd,  
5 MoW/AlNd, or MoW/Al, wherein Mo and MoW are top layers, while AlNd and Al are bottom layers.

8. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said etching of said molybdenum-containing metal layer  
10 is detected by an end-point detection method at an wavelength of about 704nm.

9. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said gas mixture is oxygen/fluorine containing.

15 10. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said gas mixture is oxygen/chlorine containing.

11. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said gas mixture is oxygen/chlorine/fluorine containing.  
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12. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said gas mixture is SiF<sub>6</sub>/O<sub>2</sub> containing.

13. (Previously amended) A front-end array process for making a liquid crystal display  
25 panel, comprising:

depositing a molybdenum-containing metal layer on a glass substrate;

forming a patterned photoresist and defining a gate and word line array pattern on said molybdenum-containing metal layer; and

etching said molybdenum-containing metal layer by using fluorine/oxygen containing  
30 gas mixture containing SF<sub>6</sub>/O<sub>2</sub> with a ratio of about 700sccm/300sccm, and using said patterned photoresist as an etching mask to form said gate and word line array pattern.

14. (Previously presented) The front-end array process for making a liquid crystal display panel according to claim 13 wherein said gate and word line array pattern have substantially oblique sidewalls.

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15. (Original) The front-end array process for making a liquid crystal display panel according to claim 13 wherein after said etching of said molybdenum-containing metal layer, an over etching is carried out.

10 16. (canceled)

17. (Original) The front-end array process for making a liquid crystal display panel according to claim 13 wherein said etching of said molybdenum-containing metal layer is executed under a process pressure higher than 25 mTorr.

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18. (Original) The front-end array process for making a liquid crystal display panel according to claim 13 wherein said etching of said molybdenum-containing metal layer is detected by an end-point detection method at an wavelength of about 704nm.

20 19. (Original) The front-end array process for making a liquid crystal display panel according to claim 13 wherein said molybdenum-containing metal layer is a dual-metal layer.

25 20. (Previously presented) The front-end array process for making a liquid crystal display panel according to claim 19 wherein said dual-metal layer is Mo/AlNd, MoW/AlNd, or MoW/Al, wherein Mo and MoW are top layers, while AlNd and Al are bottom layers.